

Resource Summary Report

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UConn Nanofabrication Facility

RRID:SCR_012346

Type: Tool

Proper Citation

UConn Nanofabrication Facility (RRID:SCR_012346)

Resource Information

URL: <http://www.scienceexchange.com/facilities/nanofabrication-facility>

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Description: THIS RESOURCE IS NO LONGER IN SERVICE. Documented on May 16, 20224. Nanofabrication Facility houses three instruments for patterning of flat surfaces and selective etching of materials. Researchers fabricate devices and structures to demonstrate novel device concepts and to characterize new materials. To carry out these functions this new facility consists of three instruments: a Tescan Electron-Beam Lithography Tool, an OAI high resolution Mask Aligner and Advanced Vacuum/Plasma Therm Reactive Ion Etcher.

Abbreviations: UConn Nanofabrication Facility

Synonyms: UConn Biotechnology - Bioservices Center Nanofabrication Facility, University of Connecticut Biotechnology - Bioservices Center Nanofabrication Facility

Resource Type: core facility, service resource, access service resource

Keywords: electron beam lithography, optical lithography, reactive ion etching

Availability: THIS RESOURCE IS NO LONGER IN SERVICE

Resource Name: UConn Nanofabrication Facility

Resource ID: SCR_012346

Alternate IDs: SciEx_11967

Record Creation Time: 20220129T080309+0000

Record Last Update: 20260801T191215+0000

Ratings and Alerts

No rating or validation information has been found for UConn Nanofabrication Facility.

No alerts have been found for UConn Nanofabrication Facility.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.